

## **W1.1 Image Quality of Printers**

INCITS W1.1 2004-023

Gloss and Gloss Uniformity

Yee Ng, Dec 6, 2004

### **Gloss/Gloss Uniformity Ad Hoc Teleconference Meeting Notes:**

(11/23/2004 teleconferences)

Present: Yee Ng (Chair, NexPress), Ming-Kai Tse (QEA), Chunghui Kuo (Nexpress), T. Graczyk (Arkwright).

Absent members:

Mike Pointer (National Physical Lab, UK), Pashant Mehta (ImageExpert), John Kessler (Paxar), Sanjay Monie (W.R. Grace), Michael Viola (Cabot Corp), Eric Zeise (Nexpress), Frans Gaykema (Oce, Netherland), Tetsuya Itoh (KonicaMinolta, Japan), Luke Cui (Lexmark), Eric Maggard (HP), Peter Morris (HP), Dale Mashtare (Xerox)

Next Teleconference: Tuesday, Dec 7, 2004 @ 1:30 EST.

#### **Agenda:**

- (1) Status of the gloss artifact round-robin experiment and the gloss/haze experiment.
- (2) Status of the 60/75 degree gloss measurement.
- (3) DOI gloss uniformity discussion

The gloss uniformity ad hoc team met on 11/23/2004 and approved the agenda. The team welcome new interested parties (M. Tse {QEA} and T. Graczyk {Arkwright}) to the teleconference. YN reported that the 8 test pages for G60/G75 measurements have been sent by Ito-san (Konica-Minolta) from Japan for our round-robin experiment. YN will send the test pages around to the other team members for measurement once he has completed his measurements. The Japan Workgroup (WG4) has measured the 8 test pages themselves using a variety of G60 and G75 gloss-meters make by different manufacturers. WG4 is in the process of measuring the 2 US samples (the one that have gone through the round-robin experiments in the US). Basic indication from WG4 is that the G60 measurements appear to have less variability between G60 gloss-meters than the G75 instruments. The G75 instruments are somewhat consistent if the gloss-meters are made by the same manufacturer and of the same model. W1 members are in the process of confirming that. YN has informed Ito-san about the method that Professor Arney has proposed to figure out the actual capture cone-angle of the gloss-meters without destructive testing. If the method can be used successfully, then correlation between gloss-meters make by different manufacturer (of a different design) can be made. A correlated and calibrated system (against a widely used instruments – such as Byk Gardner gloss-meter) can then be used for standard measurement of gloss uniformity.

CK reports on the completion of the Gloss artifact round-robin test and the result and samples will be sent to DM to prepare for the final presentation for EI2005.

MT (QEA) brought up the subject of DOI gloss artifact and its potential need to be included in the Standard (especially objective/subjective correlation standard such as ISO/IEC 19751-2). TG (Arkwright) has expressed interest to have further discussion in this area. MT and TG will discuss offline on this subject and come back to the gloss uniformity team with a more solid proposal for discussion.

Next call-in conference: Tuesday, Dec 7, 2004, 1:30PM EST.

Proposed agenda:

- (1) Status of the gloss artifact round-robin experiment.
- (2) Status of the G6/G75 measurements.
- (3) EI2005 final count-down
- (4) Follow through with DOI.

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